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INFORMATION DISCLOSURE STATEMENT
IN A PATENT
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Applicants
Fuchs et al.

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1762

U.S. PATENT DOCUMENTS

Examiner's Initials		Document Number	Date	Name	Class	Subclass	Filing Date If appropriate
<i>MBE</i>	AA	3,825,763	07/23/74	Lichtenberg et al.			
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

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FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
<i>MBE</i>	AL	OS 198 52 326	11/18/99	Germany				
<i>MBE</i>	AM	PS 195 16 450	08/08/96	Germany				
<i>MBE</i>	AN	PS 42 19 347	05/02/96	Germany				
<i>MBE</i>	AO	0 698 932	02/28/96	Europe				
<i>MBE</i>	AP	0 175 578	12/27/90	Europe				
	AQ							

OTHER PRIOR ART (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>MBE</i>	AR	Vapour-Deposited CsI:Na Layers, I. Morphologic and Crystallographic Properties, Stevels et al., Philips Res. Repts. 29 (1974) pp. 340-352					
<i>MBE</i>	AS	Vapour-Deposited CsI:Na Layers, II. Screens for Application in X-ray Imaging Devices, Stevels et al., Philips Res. Repts. 29 (1974) pp. 353-362					
<i>MBE</i>	AT	Computersimulation des Photonentransports in CsI-Eingangsschirmen von Röntgenbildverstärkern, Eckenbach, Unsere Forschung in Deutschland (Philips) Vol. IV (1989) pp 51-53					
<i>MBE</i>	AU	Effect of the Mobility of Metal Atoms on the Structure of Thin Films Deposited at Oblique Incidence, van de Waterbeemd et al., Philips Res. Repts. Vol. 22 (1967) pp. 375-387					
<i>MBE</i>	AV	Evolutionary Selection, A Principle Governing Growth Orientation in Vapour-Deposited Layers, van der Drift, Philips Res. Repts. Vol. 22 (1967) pp. 267-268					
	AW						
	AX						
	AY						
	AZ						

Examiner *M. J. Chell*

Date Considered 9/18/02 7/13/03

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.